

STRUCTURE AND METHOD OF CORRECTING PROXIMITY EFFECTS IN A
TRI-TONE ATTENUATED PHASE-SHIFTING MASK

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ABSTRACT OF THE INVENTION

A structure and method are provided for correcting the optical proximity effects on a tri-tone attenuated phase-shifting mask. An attenuated rim, formed by an opaque region and an attenuated phase-shifting region, can be kept at a predetermined width across the mask or for certain types of structures. Typically, the attenuated rim is made as large as possible to maximize the effect of the attenuated phase-shifting region while still preventing the printing of larger portions of the attenuated phase-shifting region during the development process.